

REMARKS

Applicant respectfully requests entering of the foregoing specification and claim amendment prior to examination of the present application.

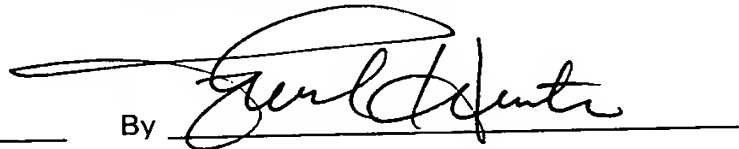
Applicant believes that the present application is now in condition for allowance. Favorable reconsideration of the application as amended is respectfully requested.

The Examiner is invited to contact the undersigned by telephone if it is felt that a telephone interview would advance the prosecution of the present application.

Respectfully submitted,

Date May 24, 2002

By



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MARKED UP AMENDED SPECIFICATION PARAGRAPH

[0021] Another exemplary embodiment is related to a method of enhancing clear field phase shift masks with a chrome border around outside edges of phase 0 and phase 180 regions. The method can include assigning phase polarities to phase areas where the phase areas include first phase areas and second phase areas, defining edges of the assigned phase areas, establishing a first boundary around the [added] defined edges of the first phase area, forming a chrome border in the first boundary around the first phase area, establishing a second boundary around the added edges of the second phase area, and forming a phase shift border in the second boundary around the second phase area.

MARKED UP AMENDED CLAIMS

1 3. (Once Amended) The method of claim 1, further comprising:
2 assigning phase polarities to phase regions;
3 defining edges of the assigned phase regions;
4 establishing a boundary around the [added] defined edges; and
5 assigning area outside of the established boundary to have phase zero.

1 17. (Once Amended) A method of enhancing clear field phase shift masks
2 with a chrome border around outside edges of phase 0 and phase 180 regions, the
3 method comprising:
4 assigning phase polarities to phase areas, the phase areas including first
5 phase areas and second phase areas;
6 defining edges of the assigned phase areas;
7 establishing a first boundary around the [added] defined edges of the first
8 phase area;
9 forming a chrome border in the first boundary around the first phase area;
10 establishing a second boundary around the added edges of the second
11 phase area; and
12 forming a phase shift border in the second boundary around the second
13 phase area.

1 18. (Once Amended) The method of claim 17, wherein [adding] defining
2 edges [to] of the assigned phase areas includes defining break regions where phase
3 transitions occur and generating polygons including edges but excluding break regions,
4 wherein the polygons are merged with the assigned phase areas.

1 24. (Once Amended) The mask of claim 22, wherein the second chrome
2 boundary region includes an opaque material.